CFI S Plan Fluor series

The broadband multilayer coating realizes high transmittance from ultraviolet to near-infrared wavelengths, with superior chromatic correction. The correction collar allows these objectives to be used with a diverse range of culture vessels and specimen thicknesses. High-quality images with no aberrations can be obtained under a broad range of illumination techniques.

CFI S Plan Fluor LWD 20XC and LWD ADM 20XC

CFI S Plan Fluor ELWD 20XC, 40XC and 60XC


CFI S Plan Fluor ELWD ADM 20XC, 40XC and ADL 60XC

Nikon Advanced Modulation Contrast (NAMC) series

Nikon has developed dedicated objectives for advanced modulation contrast. Colorless and transparent samples can be observed in high relief with a plastic dish, which is not possible in DIC observation. The direction of contrast can be matched to S Plan Fluor ELWD NAMC objectives, thereby allowing optimal contrast selection for techniques like microinjection and ICSI.

CFI S Plan Fluor ELWD NAMC 20XC and 40XC

CFI NAMC 10XF, CFI LWD NAMC 20XF and 40XC

Use	Model	NA	W.D. (mm)	Cover glass thickness	Spring loaded	Brightfield	Darkfield	DIC	Phase contrast	Polarizing	Fluorescence		Ti2-E PFS
											UV	Visible light	
Brightfield (CFI S Plan Fluor)	LWD 20XC	0.70	2.30-1.30	0-1.80		◎	○●	○		○	◎	◎	●
	ELWD 20XC	0.45	8.20-6.90	0-2.00		◎	○●	○		○	◎	◎	●
	ELWD 40XC	0.60	3.60-2.80	0-2.00		◎	○●	○		○	◎	◎	●
	ELWD 60XC	0.70	2.60-1.80	0.10-1.30		◎	○●	○		○	◎	◎	
Apodized phase contrast (CFI S Plan Fluor)	LWD ADM 20XC	0.70	2.30-1.30	0-1.80		○	○●		◎ PH2		○	○	●
	ELWD ADM 20XC	0.45	8.20-6.90	0-2.00		○	○●		◎ PH1		○	○	●
	ELWD ADM 40XC	0.60	3.60-2.80	0-2.00		○	○●		◎ PH2		○	○	●
	ELWD ADL 60XC	0.70	2.60-1.80	0.10-1.30		○	○●		◎ PH2		○	○	
Advanced modulation contrast (CFI S Plan Fluor)	ELWD NAMC 20XC	0.45	8.20-6.90	0-2.00		○					○	○	
	ELWD NAMC 40XC	0.60	3.60-2.80	0-2.00		○					○	○	
Advanced modulation contrast (CFI)	NAMC 10XF	0.25	6.20	1.20		○						●	
	LWD NAMC 20XF	0.40	3.10	1.20		○						●	
	LWD NAMC 40XC	0.55	2.70-1.70	0-2.00		○						●	